

Preparation of $({}^i\text{PrMe}_2\text{Si})_3\text{CH}$ and its use as a source of the bulky ligand $({}^i\text{PrMe}_2\text{Si})_3\text{C}$

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Abstract

The compound $({}^i\text{PrMe}_2\text{Si})_3\text{CH}$ has been made, and shown to be metallated slowly by MeLi in refluxing THF to give the lithium reagent $({}^i\text{PrMe}_2\text{Si})_3\text{CLi}$. That the latter can be used to attach the bulky ligand $({}^i\text{PrMe}_2\text{Si})_3\text{C}$ to a metalloid or metal centre was demonstrated by treating it with Me_2SiHCl to give a 77% yield of $({}^i\text{PrMe}_2\text{Si})_3\text{CSiMe}_2\text{H}$, which with iodine gave the iodide $({}^i\text{PrMe}_2\text{Si})_3\text{CSiMe}_2\text{I}$. Reactions of $({}^i\text{PrMe}_2\text{Si})_3\text{CLi}$ with Me_3SiCl and SiCl_4 likewise gave $({}^i\text{PrMe}_2\text{Si})_3\text{CSiMe}_3$ and $({}^i\text{PrMe}_2\text{Si})_3\text{CSiCl}_3$ in ca. 33% and 16% yields, respectively.

Keywords: Silicon; Steric hindrance; Bulky ligand

1. Introduction

Much novel chemistry has emerged from studies of compounds in which the bulky ligand $(\text{Me}_3\text{Si})_3\text{C}$, or to a lesser extent the related ligand $(\text{PhMe}_2\text{Si})_3\text{C}$, is attached to a metal or metalloid centre [1–4]. In order to make available an even more bulky ligand we have made the compound $({}^i\text{PrMe}_2\text{Si})_3\text{CH}$, **1**, and shown that it can be metallated to give the reagent $({}^i\text{PrMe}_2\text{Si})_3\text{CLi}$, which can be used to attach the ligand $({}^i\text{PrMe}_2\text{Si})_3\text{C}$ to a functional silicon centre.

2. Results and discussion

In a procedure analogous to that now used to make $(\text{Me}_3\text{Si})_3\text{CH}$ and $(\text{PhMe}_2\text{Si})_3\text{CH}$ [4], we made **1** by the reaction between BuLi, CHBr_3 , and ${}^i\text{PrMe}_2\text{SiCl}$ in THF, initially at -78°C ; it was obtained as an oil in 60% yield.

Lithiation of **1** by MeLi in THF proved to be much slower than that of $(\text{Me}_3\text{Si})_3\text{CH}$. Thus when a mixture of **1** with an equimolar amount of MeLi in THF was

refluxed (conditions that result in virtually quantitative lithiation of $(\text{Me}_3\text{Si})_3\text{CH}$ within 6 h [5]), initially for 12 h, and after addition of a further equimolar amount of MeLi for a further 12 h, subsequent treatment with D_2O gave approximately a 1:1 mixture of $({}^i\text{PrMe}_2\text{Si})_3\text{CH}$ and $({}^i\text{PrMe}_2\text{Si})_3\text{CD}$, indicating that metallation had been only half complete. In another experiment, after reaction between $({}^i\text{PrMe}_2\text{Si})_3\text{CH}$ and an equimolar amount of MeLi in THF had been allowed to proceed for 6 h under reflux, a sample of the mixture was withdrawn and treated with an excess of Me_2SiHCl . The product was shown by ${}^1\text{H}$ NMR spectroscopy to be a 17:83 mixture of $({}^i\text{PrMe}_2\text{Si})_3\text{CSiMe}_2\text{H}$ and $({}^i\text{PrMe}_2\text{Si})_3\text{CH}$, indicating that lithiation was ca. 17% complete. At intervals further additions of MeLi were made and further samples withdrawn for analysis, with the results shown in Table 1. It can be seen that the extent of lithiation reached a maximum of 80% after addition of a total of 3 molar equivalents of MeLi and 48 h under reflux and then, after addition of another 0.5 equivalents of MeLi, remained roughly constant during a further 24 h under reflux. Evidently the rate of decomposition of the MeLi is comparable with that of metallation, and ultimately decomposition of $({}^i\text{PrMe}_2\text{Si})_3\text{CLi}$ seems to limit its yield under these conditions, though a better yield could perhaps be obtained by initial use of a large excess of MeLi.

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Table 1

Reaction of 12.7 mmol of **1** with MeLi in refluxing THF, showing at various times the ratio ($^1\text{PrMe}_2\text{Si}$)₃CSiMe₂H:($^1\text{PrMe}_2\text{Si}$)₃CH, *R*, after treatment of a sample of the reaction mixture with Me₂SiHCl

Time (h)	MeLi (added/mmol)	<i>R</i>
0	12.7	
6		17:83
12	12.7	
24	6.3	50:50
36	6.3	
48	3.2	80:20
60	3.2	
70		78:22

In order to show that the ($^1\text{PrMe}_2\text{Si}$)₃CLi could be used to attach the new bulky ligand to a functional metalloid centre, after a metallation of ($^1\text{PrMe}_2\text{Si}$)₃CH involving several additions of MeLi and refluxing for a total of 48 h, addition of an excess of Me₂SiHCl gave, after work up, ca. an 80:20 mixture of ($^1\text{PrMe}_2\text{Si}$)₃CSiMe₂H and ($^1\text{PrMe}_2\text{Si}$)₃CH. The latter was distilled out to leave reasonably pure ($^1\text{PrMe}_2\text{Si}$)₃CSiMe₂H as a liquid. Treatment of the latter with iodine in CCl₄ then gave a good yield of the solid iodide, ($^1\text{PrMe}_2\text{Si}$)₃CSiMe₂I. (It is noteworthy that the chemical shift for the SiMe₂I protons, δ 0.43, is significantly smaller for this iodide than for for (Me₃Si)₃CSiMe₂I, δ 1.03.) Reactions of ($^1\text{PrMe}_2\text{Si}$)₃CLi with Me₃SiCl and SiCl₄ gave lower yields of ($^1\text{PrMe}_2\text{Si}$)₃CSiMe₃ (33%) and ($^1\text{PrMe}_2\text{Si}$)₃CSiCl₃ (13%), and only unchanged ($^1\text{PrMe}_2\text{Si}$)₃CH was recovered from the reaction with Me₂SiCl₂. It seems that ($^1\text{PrMe}_2\text{Si}$)₃CLi is somewhat less reactive than (Me₃Si)₃CLi, which reacts readily and quantitatively with Me₃SiCl and Me₂SiCl₂, but more reactive than (PhMe₂Si)₃CLi, which reacts with neither of these halides [6].

Although the relative difficulty of metallating ($^1\text{PrMe}_2\text{Si}$)₃CH may tend to restrict the use of the ligand ($^1\text{PrMe}_2\text{Si}$)₃C, the extra bulk of the ligand could serve to bestow particularly unusual properties on compounds containing it.

3. Experimental details

3.1. Preparation of ($^1\text{PrMe}_2\text{Si}$)₃CH, **1**

Tribromomethane was shaken several times with water to remove EtOH (present as a stabilizer), dried over CaCl₂, and distilled under reduced pressure. A 2.5 M solution of BuLi in hexane (240 cm³, 0.60 mol of BuLi) cooled to -78°C was added dropwise under nitrogen to a vigorously stirred solution of CHBr₃ (15.8 cm³, 0.18 mol) and $^1\text{PrMe}_2\text{SiCl}$ (75 g, 0.53 mol) in anhydrous THF (300 cm³) kept at -78°C. When the addition was complete, the stirred mixture was allowed

to warm overnight to room temperature and 10% aqueous hydrochloric acid was cautiously added with stirring and cooling. The organic layer was separated, washed with water, dried, and filtered. Volatile materials were distilled off under reduced pressure and the residue carefully distilled at 118–20°C at 2 mm Hg to give tri(isopropyltrimethylsilyl)methane, **1**, as a colourless liquid (35 g, 60%). Anal. Found: C, 60.7; H, 12.65. Calc. for C₁₆H₄₀Si₃: C, 60.7; H 12.7%. $\delta(\text{H})$ (CDCl₃) – 0.31 (1H, s, CH), 0.095 (18H, s, SiMe₂), 0.96 (18H, s, Me₂CH). *m/z* 301 (10%, M – Me), 273 (100, M – Pr), 231 (45), 189 (30), 129 (25), 115 (15), 73 (45), 59 (20).

3.2. Metallation of **1**

(a) A 1.4 M solution of MeLi in hexane in Et₂O (4.5 cm³, 6.3 mmol) was added dropwise under nitrogen to a solution of **1** (2.0 g, 6.3 mmol) in anhydrous THF (10 cm³), the Et₂O was distilled out, and the remaining solution was refluxed for 12 h. Further MeLi (6.3 mmol) was then added, the Et₂O distilled out as before, and the solution again refluxed for 12 h before being allowed to cool to room temperature. A solution of D₂O (0.30 g, 15 mmol) in THF (5 cm³) was cautiously added with stirring and cooling. The mixture was stirred at room temperature for 1 h and an excess of aqueous NH₄Cl was then added, followed by Et₂O (50 cm³). The organic layer was washed with water, dried (MgSO₄), and evaporated, to leave a liquid that was shown by its mass spectrum to contain ($^1\text{PrMe}_2\text{Si}$)₃CH and ($^1\text{PrMe}_2\text{Si}$)₃CD in ca. 50:50 ratio. As expected the 1H NMR spectrum was identical with that of ($^1\text{PrMe}_2\text{Si}$)₃CH except that the integral of the signal from the CH proton was roughly halved.

(b) The amounts of a 1.4 M solution of MeLi in Et₂O shown in Table 1 were added at intervals under nitrogen to a solution of **1** (4.0 g, 12.7 mmol) in THF (20 cm³); after each addition the Et₂O was distilled out, the solution refluxed for the time shown, a sample then withdrawn and added to an excess of Me₂SiHCl, and the mixture kept at room temperature for 1 h; the 1H NMR spectrum was then recorded to reveal the ratio of ($^1\text{PrMe}_2\text{Si}$)₃CSiMe₂H to ($^1\text{PrMe}_2\text{Si}$)₃CH. The results are shown in Table 1.

3.3. Preparation of ($^1\text{PrMe}_2\text{Si}$)₃CSiMe₂H

As described above, to a solution of ($^1\text{PrMe}_2\text{Si}$)₃CH (6.0 g, 19 mmol) in THF (30 cm³) under nitrogen were added at intervals appropriate amounts of a 1.4 M solution of MeLi in Et₂O (19 mmol initially; 19 mmol after 12 h; 9.5 mmol after 24 h; and 9.5 mmol after 36 h). After each addition the Et₂O was distilled out and the mixture was refluxed until the next addition. After the final addition, refluxing was carried on for 12 h, making a total reflux time of 48 h. The mixture was

subsequently cooled to room temperature, a solution of Me_2SiHCl (5.6 g, 60 mmol) in THF (10 cm^3) added dropwise, and the mixture stirred at room temperature for 1 h. Volatile organosilicon compounds (residual Me_2SiHCl and formed Me_3SiH) were distilled out, the solution was cooled, and aqueous NH_4Cl was cautiously added dropwise with stirring. Addition of ether, followed by separation, washing, drying, and evaporation of the organic layer left a liquid, which was shown by ^1H NMR spectroscopy to be an ca. 80:20 mixture of $(^1\text{PrMe}_2\text{Si})_3\text{CSiMe}_2\text{H}$ and $(^1\text{PrMe}_2\text{Si})_3\text{CH}$. The latter was distilled out under reduced pressure to leave, as a liquid, dimethyl[tri(isopropyl dimethylsilyl)methyl]silane (5.5 g, 77%). $\delta(\text{H})$ (CDCl_3) 0.25 (18H, s, SiMe_2), 0.40 (6H, d, $J = 1$ Hz, SiMe_2H), 1.04 (18H, d, $J = 2$ Hz, Me_2CH), 4.40 (1H, m, SiH). m/z 331 (50%, M – Pr), 218 (5), 215 (10), 187 (25), 173 (15), 171 (10), 130 (10), 129 (25), 101 (10), 98 (10), 73 (100), 69 (20), 59 (40).

3.4. Preparation of $(^1\text{PrMe}_2\text{Si})_3\text{CSiMe}_2\text{I}$

A solution of I_2 (11 mmol) in CCl_4 (80 cm^3) was added with stirring to a solution of $(^1\text{PrMe}_2\text{Si})_3\text{CSiMe}_2\text{H}$ (2.0 g, 5.3 mmol) in CCl_4 (20 cm^3) containing PhSiMe_3 (0.8 g, 5.3 mmol) to take up generated HI. (This may not be necessary.) The mixture was stirred for 72 h at room temperature, then shaken with aqueous NaHSO_3 to remove residual iodine. The organic layer was separated, washed, and dried (MgSO_4), and the solvent was then evaporated off under reduced pressure. The solid residue was recrystallized twice from EtOH to give $(^1\text{PrMe}_2\text{Si})_3\text{CSiMe}_2\text{I}$ (1.9 g, 71%), as a white solid that sublimed at 300°C without melting. Anal. (Found: C, 43.5, H 8.8. Calc. for $\text{C}_{18}\text{Si}_4\text{H}_{45}\text{I}$: C, 43.2; H, 9.0%. $\delta(\text{H})$ (CDCl_3) 0.35 (18H, s, SiMe_2Pr), 0.43 (6H, s, SiMe_2I), 1.06 (18H, d, $J = 6$ Hz, SiCHMe_2).

3.5. Reactions of $(^1\text{PrMe}_2\text{Si})_3\text{CLi}$ with Me_3SiCl , Me_2SiCl_2 , and SiCl_4

(a) To a solution of $(^1\text{PrMe}_2\text{Si})_3\text{CLi}$ in THF (10 cm^3), prepared from $(^1\text{PrMe}_2\text{Si})_3\text{CH}$ (19 mmol) as described above for the reaction with Me_2SiHCl , was added dropwise with cooling, a solution of Me_3SiCl (60

mmol) in THF (10 cm^3). The mixture was refluxed for 5 h then worked up as above to give a liquid that was shown by ^1H NMR spectroscopy and GLC-MS (2 m of 3% OV-17 at 230°C) to be a ca. 67:33 mixture of $(^1\text{PrMe}_2\text{Si})_3\text{CH}$ and $(^1\text{PrMe}_2\text{Si})_3\text{CSiMe}_3$. For the latter: $\delta(\text{H})$ (CDCl_3) 0.13 (9H, s, SiMe_3), 0.15 (18H, s, SiMe_2), 1.10 (18H, d, $J = \text{CHMe}_2$). m/z 345 (60%, M – Pr), 271 (15), 215 (10), 187 (35), 129 (25), 101 (5), 73 (100) and 59 (35).

(b) When the procedure was repeated, but starting from SiCl_4 , a ca. 84:16 mixture of $(^1\text{PrMe}_2\text{Si})_3\text{CH}$ and $(^1\text{PrMe}_2\text{Si})_3\text{CSiCl}_3$ was obtained. For the latter: $\delta(\text{H})$ (CDCl_3) 0.19 (18H, s, SiMe_2), 1.04 (18H, d, $J = 2$ Hz, CHMe_2). m/z 405 (45%, M – Pr), 269 (55), 187 (35), 129 (25) 101 (5), 93 (10), 73 (100), 59 (45).

(c) When the procedure was repeated but starting from Me_2SiCl_2 , only unchanged $(^1\text{PrMe}_2\text{Si})_3\text{CH}$ was present at the end.

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